

Docket No.: 43889-936

**PATENT****IN THE UNITED STATES PATENT AND TRADEMARK OFFICE**

In re Application of

Takahiro MATSUO, et al.

Serial No.:

(Divisional of Serial No. 09/326,541)

Group Art Unit:

Filed: April 17, 2000

Examiner:

For: PATTERN FORMING MATERIAL AND PATTERN FORMING METHOD

**INFORMATION DISCLOSURE STATEMENT**Assistant Commissioner for Patents  
Washington, DC 20231

Dear Sir:

In accordance with the provisions of 37 C.F.R. 1.56, 1.97 and 1.98, the attention of the Patent and Trademark Office is hereby directed to the references listed on the attached form PTO-1449. It is respectfully requested that the references be expressly considered during the prosecution of this application, and that the references be made of record therein and appear among the "References Cited" on any patent to issue therefrom.

This Information Disclosure Statement is being filed within three months of the U.S. filing date OR before the mailing date of a first Office Action on the merits. No certification or fee is required.

**(Divisional of Serial No. 09/326,541)**

The references were cited by or submitted to the U.S. Patent and Trademark Office in parent application Serial No. 09/326,541, filed June 7, 1999, which is relied upon for an earlier filing date under 35 USC 120. Thus, copies of these references are not attached. 37 CFR 1.98(d).

Respectfully submitted,

MCDERMOTT, WILL & EMERY

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<b>INFORMATION DISCLOSURE CITATION IN AN APPLICATION</b>  <b>(PTO-1449)</b>				ATTY. DOCKET NO <b>43889-936</b>		SERIAL NO. <b>09/551,656</b>	
				APPLICANT <b>Takahiro MATSUO, et al.</b>			
				FILING DATE <b>April 18, 2000</b>		GROUP	
<b>U.S. PATENT DOCUMENTS</b>							
EXAMINER'S INITIALS	PATENT NO.	DATE	NAME	CLASS	SUBCLASS	FILING DATE	
	5,650,261	7/97	Winkle				
	5,741,628	4/98	Matsuo				
	4,869,995	9/26/89	Shirai et al.				
	4,775,609	10/4/88	McFarland				
	5,015,559	5/14/91	Ogawa				
	5,278,029	1/11/94	Shirai et al.				
<b>FOREIGN PATENT DOCUMENTS</b>							
EXAMINER'S INITIALS	PATENT NO.	DATE	COUNTRY	CLASS	SUBCLASS	Translation	
						Yes	No
	0 691 674	1/10/96	Europe				
	0 515 212	11/25/92	Europe				
	0 519 128	12/23/92	Europe				
<b>OTHER ART (Including Author, Title, Date, Pertinent Pages, Etc.)</b>							
"Photosensitive Polymers Bearing Iminooxysulfonyl Groups. A Water Soluble Positive-Type Photoresist", by Shirai et al, Dic Markomol. Chemie. Macromolecular Chemistry and Physics, Vol. 90, No. 9, pp. 2099-2107 (1989).							
Shirai et al, 114:63167, Chemical Abstracts, America Chemical Society, Columbus, Ohio, Abstract of J. Appl. Polym. Sci. (1990), Vol. 41, No. 9-10, pp. 2527-2532.							
<b>EXAMINER</b>				<b>DATE CONSIDERED</b>			

EXAMINER: Initial if reference considered, whether or not citation is in conformance with MPEP 609; draw line through citation if not in conformance and not considered. Include copy of this form with next communication to Applicant.